

Heubach formulation No. 333-07

01/05

FUNCTION	PRODUCT	PRODUCER	PBW
Glycol ether	Dipropylene glycol monomethyl ether		2.05
	Water		6.15
Wetting agent	Tamol 165	Rohm and Haas	1.25
Neutralizing agent	Ammonia, 28%		0.10
Wetting agent	Triton CF-10	Union Carbide	0.15
Defoamer	Tego Foamex 1488	Tego Chemie	0.20
Anticorrosive pigment	HEUCOPHOS® ZAM-PLUS	Heubach	10.45
Iron oxide red	Bayferrox 120 NM	Bayer	5.05
Calcium carbonate	Atomite	Imerys	10.50
Antisettling agent	Aerosil R 972	Degussa, today Evonik	0.25
<b>Grind with a bead mill.</b>			
Acrylic	Maincote HG-54D	Rohm and Haas	54.90
Neutralizing agent	Ammonia, 28%		0.30
<b>Add to the grind.</b>			
	Water		2.00
Glycol ether	Dipropylene glycol monobutyl ether		3.10
Plasticizer	Dibutyl phthalate	Eastman	1.45
Defoamer	Tego Foamex 1488	Tego Chemie	0.40
Flash-rust inhibitor	Sodium nitrite, 15% in H <sub>2</sub> O		0.90
<b>Premix.</b>			
PU-thickener	Acrysol RM-12 W	Rohm and Haas	0.40
	Water		0.40
<b>Premix and add while mixing.</b>			
			<b>100.00</b>
<b>SPECIFICATIONS</b>			

# HEUCOPHOS<sup>®</sup> ZAM-PLUS

in acrylic resin



Water based

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## SPECIFICATIONS

Vol.-% Anticorrosive pigment reg. pigment/filler	36.0
PVC in %	30.6
PVC / CPVC	0.5
Solids in %	51.4

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